

Applicant : Ilya Perlov et al.
Serial No. : 10/666,003
Filed : September 17, 2003
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Attorney's Docket No.: 05542-189006 / 1895C3/CMP

REMARKS

In reply to the Office Action of May 5, 2004, the applicant submits the following remarks and respectfully requests reconsideration.

Claims 1-18 were rejected under 35 U.S.C. 112, first paragraph as failing to comply with the written description requirement. The claims 1-18 were rejected as containing subject matter, which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time application was filed, had possession of the claimed invention. The Examiner states that the claims are not supported because the specification fails to describe the following method steps: during a first period of time of polishing, applying a common first pressure at each portion of the substrate receiving surface, after the first period of time of polishing, reducing a pressure of at least one of the plurality of chambers while continuing to apply the first pressure to a remainder of the plurality of chambers, halting the application of positive pressure to the at least one of the plurality of chambers, after a second period of time of polishing, reducing a pressure of the remainder of the plurality of chambers, selecting the first period of time and second period of time to provide uniform polishing of the substrate.

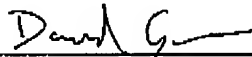
The applicant respectfully traverses the rejection and directs the Examiner's attention to lines 1-9 on page 17, where an exemplary implementation of the claimed method is described. According to the example, a pressure of 8.0 psi is applied to the inner chamber 212, the middle chamber 214, and the outer chamber 216 (a common first pressure is applied at each portion of the substrate receiving surface) for 45 seconds (a first period of time of polishing). The pressure of the outer chamber 216 (one of the plurality of chambers) is then reduced to 0 psi (halted) while a pressure of 8.0 psi is continued to be applied to the inner chamber 212 and the middle chamber 214 (i.e. the first pressure is continued to be applied to a remainder of the plurality of chambers). After another 15 seconds (a second period of time of polishing), the pressure of the inner chamber 212 and the middle chamber 214 (the remainder of the plurality of chambers) is reduced to 0 psi. The time during which positive pressure is applied to each chamber can be varied to achieve uniform polishing (see page 17, lines 1-2).

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Respectfully submitted,

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